



SHEET 1 OF 2

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0328SERIAL NO.
10/756,829APPLICANT
Robert John SOCHA, et al.FILING DATE
January 14, 2004GROUP
2825

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/S.M./		US 6,413,684 B1	07/02/2002	Stanton	
		US 6,355,382 B1	03/12/2002	Yasuzato et al.	
		US 5,229,230	07/20/1993	Kamon	
		US 5,895,741	04-20-1999	Hasegawa et al.	
		US 6,214,497 B1	04-10-2001	Stanton	
		US 2002/0152452 A1	10-17-2002	Socha	
		US 5,682,323	10-28-1997	Pasch et al.	
		US 6,303,253 B1	10-16-2001	Lu	
		US 6,223,139 B1	04-24-2001	Wong et al.	
		US 6,777,141	08-2004	Pierrat, Christophe	
		US 6,787,271	09-2004	Cote et al.	
		US 2002/0083410	06-2002	Wu et al.	
		US 6,792,591	09-2004	Shi et al.	
		US 6,519,760	02-2003	Shi et al.	
		US 2003/0228541	12-2003	Hsu et al.	
		US 2002/0157081	10-2002	Shi et al.	
		US 6,807,662	10-2004	Toubian et al.	
/S.M./		US 2004/0122636	06-2004	Adam, Konstantinos	

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number & Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.

EXAMINER

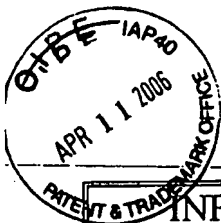
/Suresh Memula/

DATE CONSIDERED

08/28/2007

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.



SHEET 2 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 055071-0328	SERIAL NO. 10/756,829		
				APPLICANT Robert John SOCHA, et al.			
				FILING DATE January 14, 2004	GROUP 2825		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
		US					
		US					
		US					
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number + -Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No	
/S.M./		WO 02/03140 A1	01/10/2002	NUMERICAL TECHNOLOGIES, INC.		x	
/S.M./		EP 1 237 046 A2	09/04/2002	ASML MASKTOOLS B.V.		x	
/S.M./		EP 1 202 119 A1	05-02-2002	ASML Masktools B.V.		x	
/S.M./		WO 03/054826 A1	07-03-2003	ADVANCED MICRO DEVICES, INC.		x	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
/S.M./		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," Optical Microlithography XIII, Proceedings of SPIE, 2000, pp 1156-1162, Vol. 4000					
		Kyoji NAKAJO, et al., "Auxiliary pattern generation to cancel unexpected images at sidelobe overlap regions in attenuated phase-shift masks,"					
/S.M./		Nicolas Bailey COBB, "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing," Ph.D. dissertation, Spring 1998, pp 35-72, University of California at Berkeley					
		J. Fung CHEN, et al., "Practical Fine OPC Contact masks for Sub-0.3micron Design Rule Application: Part 1-OPC Design Optimization," pp 181-201					
/S.M./		J.A. TORRES, et al., "Contrast-Based Assist Feature Optimization," Optical Microlithography XV, 2002, pp 179-187, Proceedings of SPIE, Vol 4691, SPIE					
/S.M./		Olivier TOUBLAN, et al., "Fully Automatic Side Lobe Detection and Correction Technique for Attenuated Phase Shift Masks," Optical Microlithography XIV, 2001, pp 1541-1547, Proceedings of SPIE, Vol. 4346, SPIE					
/S.M./		Michael S. YEUNG, "Extension of the Hopkins theory of partially coherent imaging to include thin-film interference effects," Optical/Laser Microlithography VI, 1993, pp 452-463, SPIE, Vol. 1927					
/S.M./		Douglas VAN DEN BROEKE, et al., "Near 0.3 μ m, Full Pitch Range Contact Hole Patterning Using Chromeless Phase Lithography (CPL)," Proceedings of the SPIE, September 9, 2003, pp 297-308, Vol. 5256, SPIE					
EXAMINER /Suresh Memula/			DATE CONSIDERED 08/28/2007				

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION				ATTY. DOCKET NO. 055071-0328		SERIAL NO. 10/756,829	
(PTO-1449)				APPLICANT Robert John SOCHA, et al.			
				FILING DATE January 14, 2004		GROUP 2825	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document		Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
		US					
		US					
		US					
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code-Number-Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document		Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
/S.M./		Kyoji NAKAJO, et al., "Auxiliary pattern generation to cancel unexpected images at sidelobe overlap regions in attenuated phase-shift masks," SPIE VOL. 3748, September 1993, pp. 214-221.					
/S.M./		J. Fung CHEN, et al., "Practical I-Line OPC Contact Masks for Sub-0.3Micron Design Rule Application: Part 1—OPC Design Optimization," pp 181-201, 1997					
EXAMINER /Suresh Memula/				DATE CONSIDERED 08/28/2007			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 809. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.